EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L12	9460	430/5.ccls.	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/04/19 14:49
L13	744	430/4.ccls. not 12	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/04/19 14:50
L14	38	(12 or 13) and ((phas$3 or shift $3) near2 (mask or photomask or reticle) or $3PSM) same (substrate or base or surface) same defect$3 same (bump$3 or protru$4 or bulg$3)	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/04/19 14:52
L15	3	14 and polish$3 same (substrate or base or surface) same (defect$3 or bump$3 or protru$4 or bulg$3)	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/04/19 14:53
L16	31	14 and etch$3 same (substrate or base or surface) same (defect$3 or bump$3 or protru $4 or bulg$3) not 15	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/04/19 14:54
L17	4	14 not 15 not 16	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/04/19 14:54
L18	20	(phas$3 or shift$3) near2 defect $3 same (aggregat$3 or agglomerat$3 or collect$3 or stick$3 or stuck or adher$3) same (grain or particle or colloid $2 or silica or quartz or glass or silicon oxide or silicon dioxide or SiO".sub.2" or abrasive or abrad$3 or grind$3 or polish$3 or lap or lapping) not 15 not 16 not 17	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/04/19 15:02
L19	30	(phas$3 or shift$3) same (defect$3 or repair$3 or remov $3 or etch$3) same ((quartz or glass or silica or silicon oxide or silicon dioxide or SiO".sub.2") and (substrate or base or surface or face) and (abrasive or abrad$3 or grind$3 or polish $3 or lap or lapping) and colloid $2) not 15 not 16 not 17 not 18	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/04/19 15:14

L20	1155	356/489,495,511-514.ccls.	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/04/19 15:15
L21	16	20 and (laser or coherent or coherence) same interference same confocal	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/04/19 15:16
L22	1	(laser or coherent or coherence) same interference same confocal same (defect AND (glass or silicon dioxide or silica or SiO".sub.2")) not 14 not 15 not 16 not 17 not 18 not 19 not 21	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/04/19 15:19
L23	56	(laser or coherent or coherence) same interference same confocal same (defect OR (glass or silicon dioxide or silica or SiO".sub.2")) not 14 not 15 not 16 not 17 not 18 not 19 not 21 not 22	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/04/19 15:20
L24	8	(mask or photomask or reticle or $3PSM) same glass near2 (blank or base or substrate) same (polish$3 or abra$4 or grind$3) same (colloid$2) near2 (silica or silicon dioxide or SiO".sub.2") not 14 not 15 not 16 not 17 not 18 not 19 not 21 not 22 not 23	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/04/19 15:22
L25	16	(mask or photomask or reticle or $3PSM) same glass same (blank or base or substrate) same (polish$3 or abra$4 or grind$3) same (colloid$2) same (silica or silicon dioxide or SiO".sub.2") not 14 not 15 not 16 not 17 not 18 not 19 not 21 not 22 not 23 not 24	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/04/19 15:27
L26	3138	((mask or photomask or reticle) near3 (phas$3 or shift$3 or reflect$3 or extreme ultraviolet or extreme UV or EUV) or $3PSM) same glass not 14 not 15 not 16 not 17 not 18 not 19 not 21 not 22 not 23 not 24 not 25	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/04/19 15:27
L27	17	26 and glass same (polish$3 or abra$4 or grind$3) same (colloid$2 or grain or particle) same (silica or silicon dioxide or SiO".sub.2" or SiO$6)	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/04/19 15:29

L28	298	26 and glass same (polish$3 or abra$4 or grind$3) not 27	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/04/19 15:30
L29	682	26 and (12 or 13) and (mask or photomask or reticle or $3PSM) same glass same (blank or base or substrate) not 27 not 28	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/04/19 15:35
L30	8	29 and (polish$3 or abra$4 or grind$3) same (silica or silicon dioxide or SiO".sub.2" or silicon oxide or Si oxide)	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/04/19 15:36
L31	9433	451/36,37,41,42,390.ccls. or 65/60.1,61.ccls. or 427/160,165,290,292.ccls.	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/04/19 15:37
L32	598	31 and (polish$3 or abra$4 or grind$3) same (colloid$2) same (silica or silicon dioxide or SiO".sub.2") not 14 not 15 not 16 not 17 not 18 not 19 not 21 not 22 not 23 not 24 not 25 not 27 not 28 not 30	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/04/19 15:41
L33	66	32 and (polish$3 or abra$4 or grind$3) same (pressure or force or load) same glass	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/04/19 15:42
L34	1568	51/308.ccls.	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/04/19 15:43
L35	5	(32 or 34) and hydroly$4 same (organosilicon or organo silicon or organic silicon or organic Si) same (colloid$2) same (silica or silicon dioxide or SiO".sub.2") not 14 not 15 not 16 not 17 not 18 not 19 not 21 not 22 not 23 not 24 not 25 not 27 not 28 not 30 not 33	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/04/19 15:44
L36	3	(32 or 34) and hydroly$4 same (organosilicon or organo silicon or organic silicon or organic Si) not 14 not 15 not 16 not 17 not 18 not 19 not 21 not 22 not 23 not 24 not 25 not 27 not 28 not 30 not 33 not 35	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/04/19 15:47

L37	4	(32 or 34) and hydroly$4 near5 (silica or silicon dioxide or SIO". sub.2") same (silicon or Si) near5 (organic or polymer) not 14 not 15 not 16 not 17 not 18 not 19 not 21 not 22 not 23 not 24 not 25 not 27 not 28 not 30 not 33 not 35 not 36	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/04/19 15:48
L38	20	(32 or 34) and hydroly$4 SAME (silica or silicon dioxide or SIO". sub.2") same (silicon or Si) same (organic or polymer) not 14 not 15 not 16 not 17 not 18 not 19 not 21 not 22 not 23 not 24 not 25 not 27 not 28 not 30 not 33 not 35 not 36 not 37	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/04/19 15:51
L39	7	(mask or photomask or reticle or $3PSM) same (glass or quartz) same (blank or substrate) same (polish$3 or abra$4 or grind$3 or lap$6) same "pH" not 14 not 15 not 16 not 17 not 18 not 19 not 21 not 22 not 23 not 24 not 25 not 27 not 28 not 30 not 33 not 35 not 36 not 37 not 38	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/04/19 15:53
L40	1371607	glass or quartz	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/04/19 15:54
L41	278702	polish or polishing or polished	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/04/19 15:54
L42	692309	silica or silicon dioxide or SIO". sub.2"	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/04/19 15:55
L43	10616	40 and 41 and 42 and "pH"	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/04/19 15:56
L44	2544	41 same "pH" and 40 and 42	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/04/19 15:57
L45	1245	44 and 40 same 42	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/04/19 15:59
L46	359	45 and 41 near10 "pH" and colloidal 42	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/04/19 16:00

L47	325	(40 and 41 and 42).ti,ab.	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/04/19 16:21
L48	9	(46 and 47) not 14 not 15 not 16 not 17 not 18 not 19 not 21 not 22 not 23 not 24 not 25 not 27 not 28 not 30 not 33 not 35 not 36 not 37 not 38 not 39	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/04/19 16:24
L49	89	40 same 41 same colloid$2 42 same (silicon dioxide or SiO".sub.2") not 14 not 15 not 16 not 17 not 18 not 19 not 21 not 22 not 23 not 24 not 25 not 27 not 28 not 30 not 33 not 35 not 36 not 37 not 38 not 39 not 48	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/04/19 16:31
L50	13	49 and 41 same "pH" not 14 not 15 not 16 not 17 not 18 not 19 not 21 not 22 not 23 not 24 not 25 not 27 not 28 not 30 not 33 not 35 not 36 not 37 not 38 not 39 not 48	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/04/19 16:33
L51	24541	(quartz near3 glass) with (mask or photomask or reticle or blank or substrate or support)	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/04/19 16:35
L52	8010	(mask or photomask or reticle) with (polish$3 or lap$4)	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/04/19 16:36
L53	89	51 and 52 and excimer	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/04/19 16:36
L54	1331	(mask or photomask or reticle or blank or substrate or support) and ((pressure or weight$3 or load) with ("kg/cm.sup.2" or "g/cm.sup.2")) same (polish$3 or lap$4)	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/04/19 16:39
L55	44047	(glass or quartz) same (polish$3 or lap$4)	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/04/19 16:40
L56	514	54 and 55	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/04/19 16:41
L57	55226	colloid$2 near3 42	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/04/19 16:42

L58	1757	hydroly$4 with 57	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/04/19 16:43
L59	13	56 and 58 not 14 not 15 not 16 not 17 not 18 not 19 not 21 not 22 not 23 not 24 not 25 not 27 not 28 not 30 not 33 not 35 not 36 not 37 not 38 not 39 not 48 not 50	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/04/19 16:44
L60	1	53 and 57 not 14 not 15 not 16 not 17 not 18 not 19 not 21 not 22 not 23 not 24 not 25 not 27 not 28 not 30 not 33 not 35 not 36 not 37 not 38 not 39 not 48 not 50 not 59	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/04/19 16:47
L61	2	53 and 54 not 14 not 15 not 16 not 17 not 18 not 19 not 21 not 22 not 23 not 24 not 25 not 27 not 28 not 30 not 33 not 35 not 36 not 37 not 38 not 39 not 48 not 50 not 59 not 60	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/04/19 16:48
L62	44	57 and (glass or quartz) same (((pressure or weight$3 or load) with ("kg/cm.sup.2" or "g/cm.sup.2")) same (polish$3 or lap$4)) not 14 not 15 not 16 not 17 not 18 not 19 not 21 not 22 not 23 not 24 not 25 not 27 not 28 not 30 not 33 not 35 not 36 not 37 not 38 not 39 not 48 not 50 not 59 not 60 not 61	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/04/19 16:55
L63	27	62 and (surface roughness or root mean square or RMS)	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/04/19 16:56
L64	142	54 and 55 and 57 not 14 not 15 not 16 not 17 not 18 not 19 not 21 not 22 not 23 not 24 not 25 not 27 not 28 not 30 not 33 not 35 not 36 not 37 not 38 not 39 not 48 not 50 not 59 not 60 not 61 not 63	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/04/19 17:03
L65	45	64 and (surface roughness or root mean square or RMS)	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/04/19 17:03
L66	24	65 and "pH"	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/04/19 17:04

L67	19	(Koike-Kesahiro or Miyagaki-Junji).in. not 14 not 15 not 16 not 17 not 18 not 19 not 21 not 22 not 23 not 24 not 25 not 27 not 28 not 30 not 33 not 35 not 36 not 37 not 38 not 39 not 48 not 50 not 59 not 60 not 61 not 63 not 66	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/04/19 17:07
L68	1	(Hoya).as. and (phas$3 or shift $3 or $3PSM) and (defect$3 or protru$4 or bump or bulg$3) and polish$3 and colloid$2 near2 42 and "pH" not 14 not 15 not 16 not 17 not 18 not 19 not 21 not 22 not 23 not 24 not 25 not 27 not 28 not 30 not 33 not 35 not 36 not 37 not 38 not 39 not 48 not 50 not 59 not 60 not 61 not 63 not 66 not 67	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/04/19 17:10
L69	3	(Hoya).as. and (phas$3 or shift $3 or $3PSM) and (defect$3 or protru$4 or bump or bulg$3) and 40 and 42 and polish$3 and "pH" not 14 not 15 not 16 not 17 not 18 not 19 not 21 not 22 not 23 not 24 not 25 not 27 not 28 not 30 not 33 not 35 not 36 not 37 not 38 not 39 not 48 not 50 not 59 not 60 not 61 not 63 not 66 not 67 not 68	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/04/19 17:12
L70	0	(40 and (mask or photomask or reticle or blank or substrate or support or base or surface) and (phas$3 or shift$3 or $3PSM) and (defect$3 or protru $4 or bump or bulg$3) and (polish$3 or lap$4 or abrad$3 or abras$6 or grind$3) and (colloid$2 or grain or particle) near3 42 and (aggregat$3 or agglomerat$3 or collect$3 or stick$3 or stuck or adher$3) and "pH").clm.	US-PGPUB; USPAT	ADJ	ON	2008/04/19 17:37
L71	1	(40 and (mask or photomask or reticle or blank or substrate or support or base or surface) and (phas$3 or shift$3 or $3PSM) and (defect$3 or protru $4 or bump or bulg$3) and (polish$3 or lap$4 or abrad$3 or abras$6 or grind$3) and (colloid$2 or grain or particle) near3 42 and (aggregat$3 or agglomerat$3 or collect$3 or stick$3 or stuck or adher$3) and (pressure or weight$3 or	US-PGPUB; USPAT	ADJ	ON	2008/04/19 17:39

		load)).clm. not 70				
L72	0	(40 and (mask or photomask or reticle or blank or substrate or support or base or surface) and (phas$3 or shift$3 or $3PSM) and (defect$3 or protru $4 or bump or bulg$3) and (polish$3 or lap$4 or abrad$3 or abras$6 or grind$3) and (colloid$2 or grain or particle) near3 42 and ((pressure or weight$3 or load) or "pH")).clm. not 70 not 71	US-PGPUB; USPAT	ADJ	ON	2008/04/19 17:41

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